Thermal Evaporator
INDIUM Deposition

Evaporation takes place in a vacuum, i.e. vapors other than the source material are almost entirely removed before the process begins. In high vacuum (with a long mean free path), evaporated particles can travel directly to the deposition target without colliding with the background gas..

Process Capabilities:

- Base pressure : 4.0E-6
- Boat filament used of molybdenum
- Filament Current: vary from 120-200 Amp.

Thickness Monitoring:

- Crystal life: 80-100%
- Density : 7.30
- Acoustic impedance : 10.50
- Tooling Factor : 64%
- Deposition : 5nm to 10 micron .

Specifications

- **Substrate size**: 2'' .
- **Substrates used in chamber:** GaAs ,Si .
- **Films that can be deposited:** Oxides .
- **Target diameter**: molybdenum boats .
- **Targets available**: indium slugs .
- **Substrate temperature:** Room temp to 250°C .
- **Chamber pressure:** Up to 10-6Torr .
- **Gases used in the system:** Nitrogen (N2) .